

Sellafield big winners at global awards

The company has won 4 awards at the prestigious Institute of Chemical Engineers (IChemE) event and a highly commended in the 'Research Project' category.

The annual event celebrates the achievements of chemical engineers around the world.

The 'Process Safety Award' went to Sellafield Ltd employee, Joe Hayward, a process responsible engineer in retrievals, for his MSSS entry – helping to solve the site's decommissioning challenges.

The 'Team Award' went to Sellafield Ltd for 'Collaborating to Develop Nuclear Chemical Engineering Skills' entry, which was collected by process engineer Kathleen Feller. This entry celebrated the collaboration between Sellafield Ltd and Loughborough University in developing our engineering skills and capability.

Simon Malone, a technical assurance manager at Sellafield Ltd, came away with a highly commended for his research project 'SMART Sensors in Can Monitoring'.

And the night was topped off with Sellafield Ltd and the National Nuclear laboratories, in a joint entry, picking up the 'Overall Achievement Award' for its winning entry 'Process Flow Smoothing Optimisation of Nationally Critical Nuclear Infrastructure', which was submitted by process engineer, Jack Newton.

The 'Overall Achievement Award'.

Martin Chown, chief executive officer, Sellafield Ltd said:

These awards are a clear demonstration of the contribution our chemical engineers are making to our purpose and is a testament to our long-standing collaboration with our partners.

I'm so proud to see that our professional chemical engineering community are doing great things. Congratulations to all our deserving winners.

Chief process engineer, Sellafield Ltd, Elisabeth Cooke said:

Congratulations to all finalists and our own winners. This is great achievement for all the authors and winning teams who contributed

to representing us at these global awards.

To be recognised on this scale is tremendous and for all their contributions to make Sellafield a clean and safe environment for future generations.